

d 111 bib hitstr

L11 ANSWER 1 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 2002:595097 CAPLUS

DN 137:141802

TI Lightweight fire-resistant silicone-coated cloth and airbags

IN Ishii, Hideaki; Nagaoka, Toshirou

PA Asahi Kasei Kabushiki Kaisha, Japan

SO PCT Int. Appl., 55 pp.

CODEN: PIXXD2

DT Patent

LA Japanese

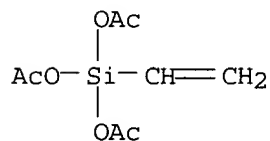
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2002061200	A1	20020808	WO 2001-JP8834	20011005
	W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM			
	RW:	GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG			
PRAI	JP 2001-26103	A	20010201		
	JP 2001-134396	A	20010501		
IT	210993-79-6, HF 86				
	RL:	TEM (Technical or engineered material use); USES (Uses) (adhesion promotor; lightwt. fire-resistant silicone-coated cloth for airbags)			
RN	210993-79-6 CAPLUS				
CN	Silanetriol, ethenyl-, triacetate, mixt. with trimethoxy[3-(oxiranylethoxy)propyl]silane (9CI) (CA INDEX NAME)				

CM 1

CRN 4130-08-9

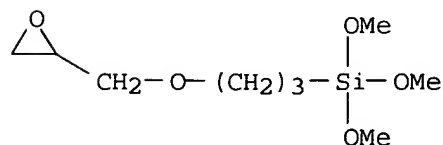
CMF C8 H12 O6 Si



CM 2

CRN 2530-83-8

CMF C9 H20 O5 Si



RE.CNT 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD

ALL CITATIONS AVAILABLE IN THE RE FORMAT

=> d l11 1-34 bib hitstr

L11 ANSWER 1 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 2002:595097 CAPLUS

DN 137:141802

TI Lightweight fire-resistant silicone-coated cloth and airbags

IN Ishii, Hideaki; Nagaoka, Toshirou

PA Asahi Kasei Kabushiki Kaisha, Japan

SO PCT Int. Appl., 55 pp.

CODEN: PIXXD2

DT Patent

LA Japanese

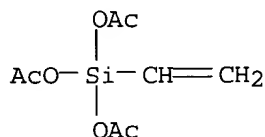
FAN.CNT 1

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PI	WO 2002061200	A1	20020808	WO 2001-JP8834	20011005
	W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
PRAI	JP 2001-26103	A	20010201		
	JP 2001-134396	A	20010501		
IT	210993-79-6, HF 86				
	RL: TEM (Technical or engineered material use); USES (Uses) (adhesion promotor; lightwt. fire-resistant silicone-coated cloth for airbags)				
RN	210993-79-6 CAPLUS				
CN	Silanetriol, ethenyl-, triacetate, mixt. with trimethoxy[3-(oxiranylethoxy)propyl]silane (9CI) (CA INDEX NAME)				

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CRN 4130-08-9

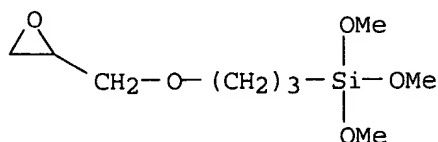
CMF C8 H12 O6 Si

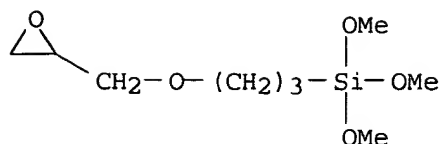


CM 2

CRN 2530-83-8

CMF C9 H20 O5 Si





RE.CNT 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L11 ANSWER 2 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 2002:591741 CAPLUS

DN 137:126563

TI Acrylic polysiloxane coating composition, cured product, laminate and method for producing the cured product

IN Shimada, Mibuko; Yoshimura, Nakaatsu; Hashiguchi, Yuichi

PA JSR Corporation, Japan

SO Eur. Pat. Appl., 27 pp.

CODEN: EPXXDW

DT Patent

LA English

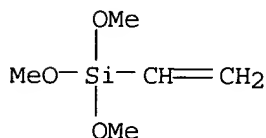
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1229092	A2	20020807	EP 2002-2262	20020130
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
PRAI	JP 2001-24780	A	20010131		
IT	307530-50-3P , Ethyl vinyl ether-Methyltrimethoxysilane-3-Glycidoxypropyltrimethoxysilane-Hexafluoropropylene-Vinyltrimethoxysilane copolymer				
	RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)				
	(manuf. of acrylic polysiloxane coating compn. for plastic films)				
RN	307530-50-3 CAPLUS				
CN	Silane, ethenyltrimethoxy-, polymer with ethoxyethene, 1,1,2,3,3,3-hexafluoro-1-propene, trimethoxymethylsilane and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)				

CM 1

CRN 2768-02-7

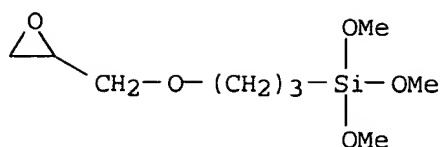
CMF C5 H12 O3 Si



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CRN 2530-83-8

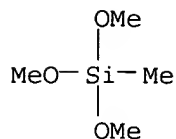
CMF C9 H20 O5 Si



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CRN 1185-55-3

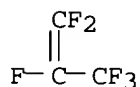
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CM 4

CRN 116-15-4

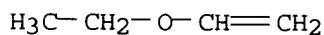
CMF C3 F6



CM 5

CRN 109-92-2

CMF C4 H8 O



L11 ANSWER 3 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 2001:830751 CAPLUS

DN 135:359189

TI Functionalized copolymers for use in coatings

IN Stark, Kurt; Tschirner, Peter; Ball, Peter; Bueppelmann, Klaus; Kotschi, Udo

PA Wacker Polymer Systems G.m.b.H. & Co. K.-G., Germany

SO Eur. Pat. Appl., 15 pp.

CODEN: EPXXDW

DT Patent

LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	---	-----	-----	-----
PI	EP 1153979	A2	20011114	EP 2001-109326	20010412
	EP 1153979	A3	20020123		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	DE 10022992	A1	20011206	DE 2000-10022992	20000511

US 2002007009 A1 20020117 US 2001-850208 20010507
 PRAI DE 2000-10022992 A 20000511
 IT **372194-93-9P**

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (functionalized copolymers for use in coatings)

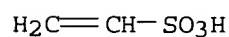
RN 372194-93-9 CAPLUS

CN Butanoic acid, 3-oxo-, 2-propenyl ester, polymer with ethene, ethenyl acetate, ethenyltrimethoxysilane, oxiranylmethyl 2-methyl-2-propenoate, sodium ethenesulfonate and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 3039-83-6

CMF C2 H4 O3 S . Na

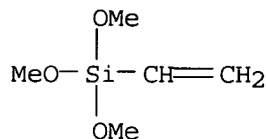


● Na

CM 2

CRN 2768-02-7

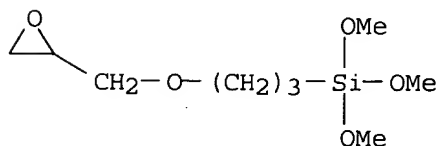
CMF C5 H12 O3 Si



CM 3

CRN 2530-83-8

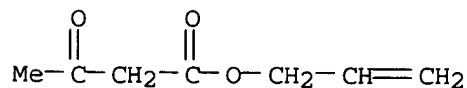
CMF C9 H20 O5 Si

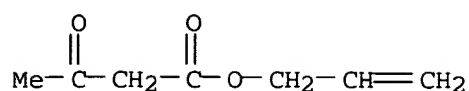


CM 4

CRN 1118-84-9

CMF C7 H10 O3





CM 5

CRN 108-05-4

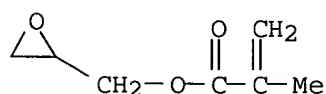
CMF C4 H6 O2



CM 6

CRN 106-91-2

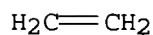
CMF C7 H10 O3



CM 7

CRN 74-85-1

CMF C2 H4



L11 ANSWER 4 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 2000:822734 CAPLUS

DN 133:363798

TI A coating composition, and a coated film and glass each having a coating layer comprised thereof

IN Shimada, Mibuko; Sakagami, Toshinori; Shiho, Hiroshi; Hashiguchi, Yuichi

PA JSR Corporation, Japan

SO Eur. Pat. Appl., 37 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1054047	A2	20001122	EP 2000-110630	20000518
	EP 1054047	A3	20011010		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	JP 2000328001	A2	20001128	JP 1999-142428	19990521
	JP 2001049173	A2	20010220	JP 1999-225915	19990810
PRAI	JP 1999-142428	A	19990521		
	JP 1999-225915	A	19990810		
IT	307530-50-3P , Ethyl vinyl ether-hexafluoropropylene-glycidoxypolytrimethoxysilane-methyltrimethoxysilane-vinyltrimethoxysilane copolymer				

RL: IMF (Industrial manufacture); PRP (Properties); PREP (Preparation)
 (coating compn. contg. polysiloxanes and vinyl polymers having good
 soilproofing and abrasion resistance)

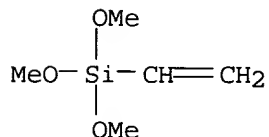
RN 307530-50-3 CAPLUS

CN Silane, ethenyltrimethoxy-, polymer with ethoxyethene,
 1,1,2,3,3,3-hexafluoro-1-propene, trimethoxymethylsilane and
 trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 2768-02-7

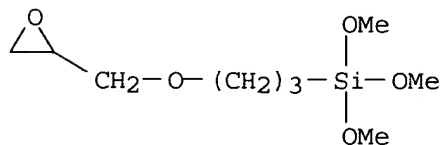
CMF C5 H12 O3 Si



CM 2

CRN 2530-83-8

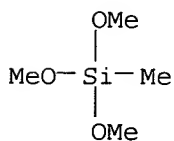
CMF C9 H20 O5 Si



CM 3

CRN 1185-55-3

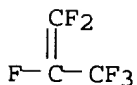
CMF C4 H12 O3 Si



CM 4

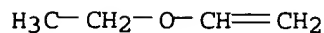
CRN 116-15-4

CMF C3 F6



CM 5

CRN 109-92-2
CMF C4 H8 O



L11 ANSWER 5 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 2000:562683 CAPLUS

DN 133:152092

TI Metallic finishing for forming glossy, weather-resistant coatings with high adhesion

IN Iida, Akito; Inukai, Hiroshi

PA Toa Gosei Chemical Industry Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000225374	A2	20000815	JP 1999-26216	19990203

IT **287475-38-1P**

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(base coat; metallic finishing using silane-crosslinkable fluoropolymer topcoats for glossy, weather-resistant coatings with high adhesion)

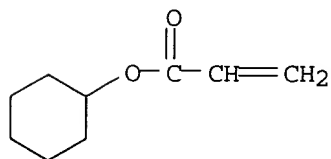
RN 287475-38-1 CAPLUS

CN 2-Propenoic acid, cyclohexyl ester, polymer with chlorotrifluoroethene, ethenyltrimethoxysilane, ethyl 2-propenoate and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 3066-71-5

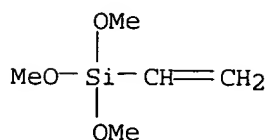
CMF C9 H14 O2



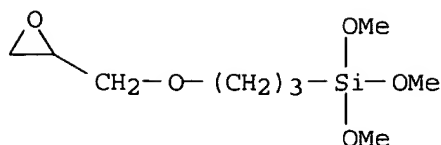
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CRN 2768-02-7

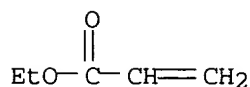
CMF C5 H12 O3 Si



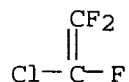
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CMF C9 H20 O5 Si



CRN 140-88-5
CMF C5 H8 O2



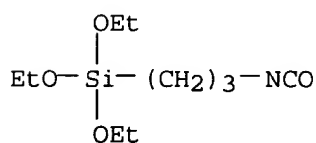
CRN 79-38-9
CMF C2 C1 F3



RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(topcoat; metallic finishing using silane-crosslinkable fluoropolymer topcoats for glossy, weather-resistant coatings with high adhesion)

CN 2-Propenoic acid, cyclohexyl ester, polymer with chlorotrifluoroethene, 1,1-dimethylethyl 2-propenoate, ethenyltrimethoxysilane, silicic acid (H4SiO4) tetraethyl ester, triethoxy(3-isocyanatopropyl)silane, trimethoxy[3-(oxiranylmethoxy)propyl]silane and rel-(1R,2R,4R)-1,7,7-trimethylbicyclo[2.2.1]hept-2-yl 2-propenoate (9CI) (CA INDEX NAME)

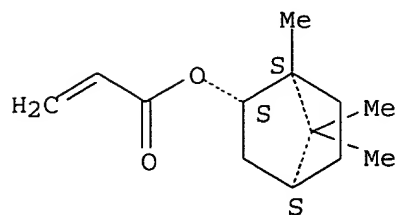
CRN 24801-88-5
CMF C10 H21 N O4 Si



CM 2

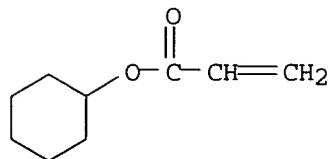
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CMF C13 H20 O2

Relative stereochemistry.



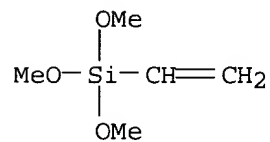
CM 3

CRN 3066-71-5
CMF C9 H14 O2



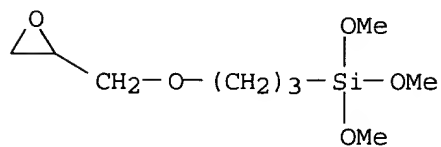
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CRN 2768-02-7
CMF C5 H12 O3 Si



CM 5

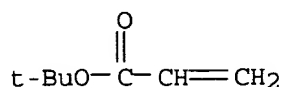
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CMF C9 H20 O5 Si



CM 6

CRN 1663-39-4

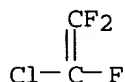
CMF C7 H12 O2



CM 7

CRN 79-38-9

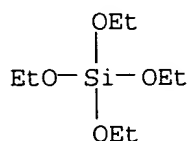
CMF C2 C1 F3



CM 8

CRN 78-10-4

CMF C8 H20 O4 Si



L11 ANSWER 6 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 2000:396569 CAPLUS

DN 133:31764

TI Aqueous emulsions for manufacture of silicone rubber coatings on textile airbags

IN Mueller, Johann; Stoemmer, Martin

PA Wacker-Chemie G.m.b.H., Germany

SO Ger. Offen., 6 pp.

CODEN: GWXXBX

DT Patent

LA German

FAN.CNT 1

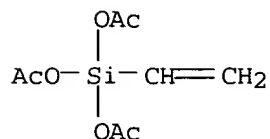
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PI	DE 19857307	A1	20000615	DE 1998-19857307	19981211
	EP 1010721	A1	20000621	EP 1999-120901	19991028
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	KR 2000047960	A	20000725	KR 1999-55429	19991207
	JP 2000169590	A2	20000620	JP 1999-350422	19991209
PRAI	DE 1998-19857307	A	19981211		
IT	69882-18-4				
	RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)				
	(adhesion improver; aq. emulsions for manuf. of silicone rubber coatings on textile airbags)				
RN	69882-18-4 CAPLUS				
CN	Silanetriol, ethenyl-, triacetate, polymer with trimethoxy[3-				

(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 4130-08-9

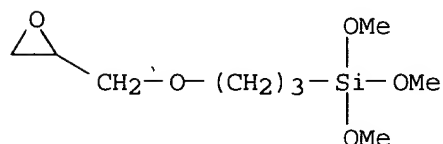
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CM 2

CRN 2530-83-8

CMF C9 H20 O5 Si



L11 ANSWER 7 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 2000:356388 CAPLUS

DN 132:349083

TI Anticorrosive and soiling- and weather-resistant coatings for metal surface

IN Iida, Akito; Inukai, Hiroshi

PA Toa Gosei Chemical Industry Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000144036	A2	20000526	JP 1998-323775	19981113

IT **269081-02-9P 269081-03-0P**

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(topcoat layer; anticorrosive and soiling- and weather-resistant coatings for metal surface)

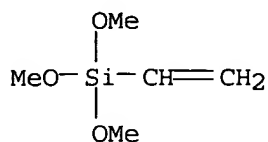
RN 269081-02-9 CAPLUS

CN Silane, ethenyltrimethoxy-, polymer with chlorotrifluoroethene, ethoxyethene and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 2768-02-7

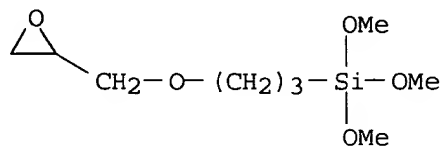
CMF C5 H12 O3 Si



CM 2

CRN 2530-83-8

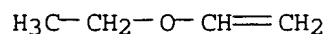
CMF C9 H20 O5 Si



CM 3

CRN 109-92-2

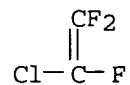
CMF C4 H8 O



CM 4

CRN 79-38-9

CMF C2 Cl F3



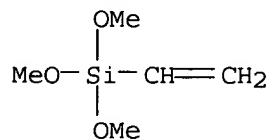
RN 269081-03-0 CAPLUS

CN Silicic acid (H₄SiO₄), tetraethyl ester, polymer with chlorotrifluoroethene, ethenyltrimethoxysilane, ethoxyethene and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

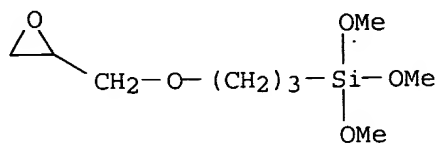
CRN 2768-02-7

CMF C5 H12 O3 Si



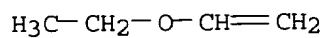
CM 2

CRN 2530-83-8
CMF C9 H20 O5 Si



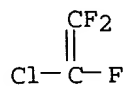
CM 3

CRN 109-92-2
CMF C4 H8 O



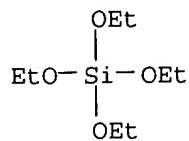
CM 4

CRN 79-38-9
CMF C2 Cl F3



CM 5

CRN 78-10-4
CMF C8 H20 O4 Si



L11 ANSWER 8 OF 34 CAPLUS COPYRIGHT 2002 ACS
AN 2000:294151 CAPLUS
DN 133:74707
TI Phase structure and thermal and mechanical properties of epoxy/silica hybrids
AU Takahashi, Ryuji; Wakita, Manami; Ochi, Mitsukazu
CS Faculty of Engineering, Kansai University, Suita-shi, Osaka, 564-8680, Japan
SO Kobunshi Ronbunshu (2000), 57(4), 220-227
CODEN: KBRBA3; ISSN: 0386-2186
PB Kobunshi Gakkai
DT Journal
LA Japanese
IT 279679-14-0

RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); PRP (Properties); PROC (Process); USES (Uses)

(prepn., phase structure, and thermal and mech. properties of epoxy/silica hybrids)

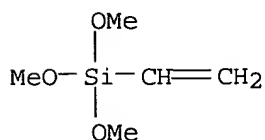
RN 279679-14-0 CAPLUS

CN 1,2-Ethanediamine, N-(2-aminoethyl)-N'-[2-[(2-aminoethyl)amino]ethyl]-, polymer with ethenyltrimethoxysilane, 2,2'-[(1-methylethylidene)bis(4,1-phenyleneoxymethylene)]bis[oxirane] and trimethoxy[3-(oxiranylethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 2768-02-7

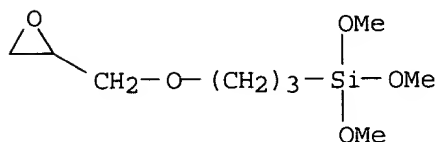
CMF C5 H12 O3 Si



CM 2

CRN 2530-83-8

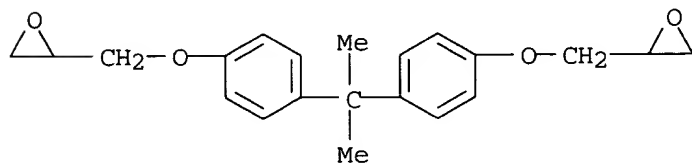
CMF C9 H20 O5 Si



CM 3

CRN 1675-54-3

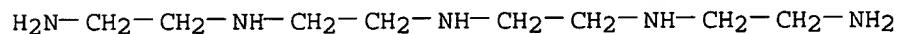
CMF C21 H24 O4



CM 4

CRN 112-57-2

CMF C8 H23 N5



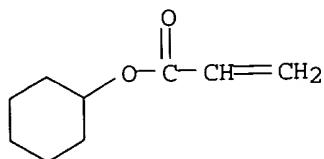
L11 ANSWER 9 OF 34 CAPLUS COPYRIGHT 2002 ACS
 AN 2000:266929 CAPLUS
 DN 132:295218
 TI Repairing process for coating films
 IN Iida, Akito; Inukai, Hiroshi
 PA Toa Gosei Chemical Industry Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 7 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000117190	A2	20000425	JP 1998-301652	19981008
IT	264199-37-3P , Chlorotrifluoroethylene-cyclohexyl acrylate-.gamma.-glycidoxypropyltrimethoxysilane-vinyltrimethoxysilane copolymer 264199-38-4P , Chlorotrifluoroethylene-cyclohexyl acrylate-.gamma.-glycidoxypropyltrimethoxysilane-.gamma.- isocyanatopropyltriethoxysilane-vinyltrimethoxysilane copolymer RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (repairing coating films with acrylic fluoro polysiloxane compns. for good adhesion) RN 264199-37-3 CAPLUS CN 2-Propenoic acid, cyclohexyl ester, polymer with chlorotrifluoroethene, ethenyltrimethoxysilane and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)				

CM 1

CRN 3066-71-5

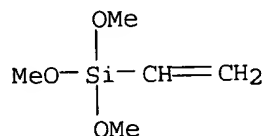
CMF C9 H14 O2



CM 2

CRN 2768-02-7

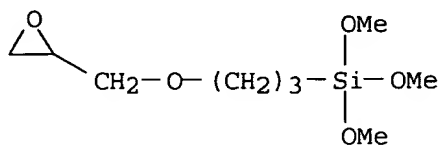
CMF C5 H12 O3 Si



CM 3

CRN 2530-83-8

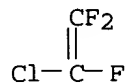
CMF C9 H20 O5 Si



CM 4

CRN 79-38-9

CMF C2 Cl F3



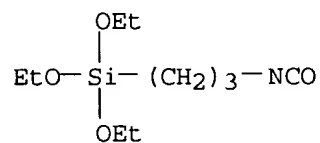
RN 264199-38-4 CAPLUS

CN 2-Propenoic acid, cyclohexyl ester, polymer with chlorotrifluoroethene, ethenyltrimethoxysilane, triethoxy(3-isocyanatopropyl)silane and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 24801-88-5

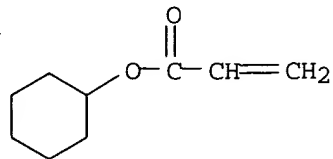
CMF Cl0 H21 N O4 Si



CM 2

CRN 3066-71-5

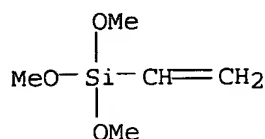
CMF C9 H14 O2



CM 3

CRN 2768-02-7

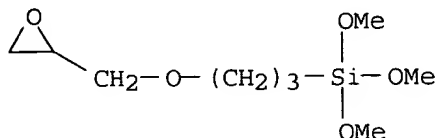
CMF C5 H12 O3 Si



CM 4

CRN 2530-83-8

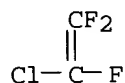
CMF C9 H20 O5 Si



CM 5

CRN 79-38-9

CMF C2 Cl F3



L11 ANSWER 10 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1999:716211 CAPLUS

DN 131:323948

TI Titania-containing organic silicon polymer compositions for hard coatings on plastic lenses and their laminates with antireflection films

IN Miyashita, Kazunori; Takeshita, Katsuyoshi

PA Seiko Epson Corp., Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11310755	A2	19991109	JP 1998-117318	19980427

IT **164065-58-1P**, (.gamma.-Glycidoxypropyl)trimethoxysilane-vinyltrimethoxysilane copolymer **249505-84-8P**

RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(titania-contg. organopolysiloxane compns. for hard coatings on plastic lenses and their laminates with antireflection films)

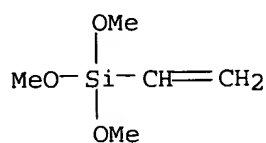
RN 164065-58-1 CAPLUS

CN Silane, ethenyltrimethoxy-, polymer with trimethoxy[3-(oxiranylethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 2768-02-7

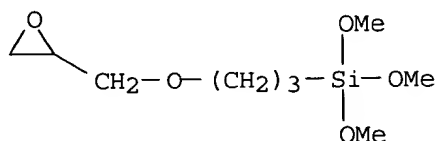
CMF C5 H12 O3 Si



CM 2

CRN 2530-83-8

CMF C9 H20 O5 Si



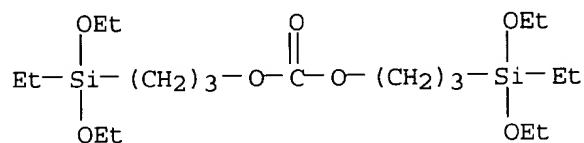
RN 249505-84-8 CAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with bis[3-(diethoxyethylsilyl)propyl] carbonate, 2-(dimethylamino)ethyl 2-methyl-2-propenoate, ethenyltrimethoxysilane, 2,2'-[1,6-hexanediylbis(oxymethylene)]bis[oxirane] and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 225663-58-1

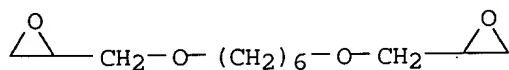
CMF C19 H42 O7 Si2



CM 2

CRN 16096-31-4

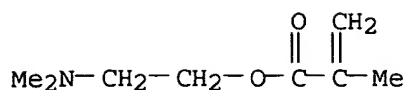
CMF C12 H22 O4



CM 3

CRN 2867-47-2

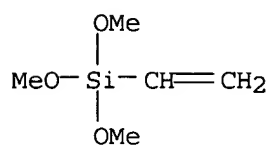
CMF C8 H15 N O2



CM 4

CRN 2768-02-7

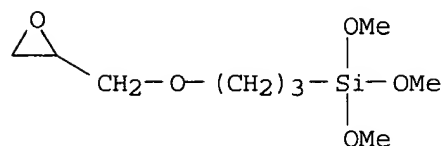
CMF C5 H12 O3 Si



CM 5

CRN 2530-83-8

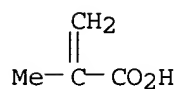
CMF C9 H20 O5 Si



CM 6

CRN 79-41-4

CMF C4 H6 O2



L11 ANSWER 11 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1999:715101 CAPLUS

DN 131:338384

TI Moisture-curable compositions for fluoropolymer coatings with good adhesion strength

IN Iida, Akito; Inukai, Hiroshi

PA Toa Gosei Chemical Industry Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11310747	A2	19991109	JP 1998-136023	19980430
IT	249619-64-5P, Chlorotrifluoroethylene-ethyl vinyl ether-(3-glycidoxypentyl)trimethoxysilane-(3-isocyanatopropyl)trimethoxysilane				

lane-vinyltrimethoxysilane copolymer

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(moisture-curable hydrolyzable silyl-contg. fluoropolymer compns. for coatings with good adhesion strength)

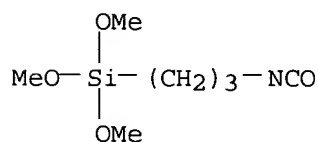
RN 249619-64-5 CAPLUS

CN Silane, ethenyltrimethoxy-, polymer with chlorotrifluoroethene, ethoxyethene, (3-isocyanatopropyl)trimethoxysilane and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 15396-00-6

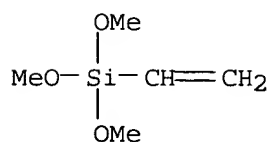
CMF C7 H15 N O4 Si



CM 2

CRN 2768-02-7

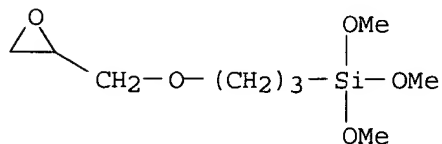
CMF C5 H12 O3 Si



CM 3

CRN 2530-83-8

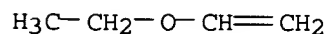
CMF C9 H20 O5 Si



CM 4

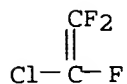
CRN 109-92-2

CMF C4 H8 O



CM 5

CRN 79-38-9
CMF C2 C1 F3



L11 ANSWER 12 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1999:481606 CAPLUS

DN 131:131341

TI Coating films with high durability and bright color

IN Kudo, Shinichi; Kinoshita, Koji; Ooka, Masataka

PA Dainippon Ink and Chemicals, Inc., Japan

SO Jpn. Kokai Tokkyo Koho, 51 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

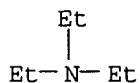
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11209693	A2	19990803	JP 1998-11262	19980123
IT	234080-03-6P , Monobutyl maleate-vinyl acetate-ethyl vinyl ether-vinyltris(.beta.-methoxyethoxy)silane-chlorotrifluoroethylene-phenyltrimethoxysilane-methyltrimethoxysilane-3-glycidoxypropyltrimethoxysilane copolymer triethylamine salt 234080-13-8P RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (coating films with high durability and bright color)				
RN	234080-03-6 CAPLUS				
CN	2-Butenedioic acid (2Z)-, monobutyl ester, polymer with chlorotrifluoroethene, ethenyl acetate, 6-ethenyl-6-(2-methoxyethoxy)-2,5,7,10-tetraoxa-6-silaundecane, ethoxyethene, trimethoxymethylsilane, trimethoxy[3-(oxiranylmethoxy)propyl]silane and trimethoxyphenylsilane, compd. with N,N-diethylethanamine (9CI) (CA INDEX NAME)				

CM 1

CRN 121-44-8

CMF C6 H15 N



CM 2

CRN 234080-02-5

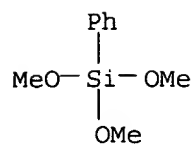
CMF (C11 H24 O6 Si . C9 H20 O5 Si . C9 H14 O3 Si . C8 H12 O4 . C4 H12 O3 Si . C4 H8 O . C4 H6 O2 . C2 Cl F3)x

CCI PMS

CM 3

CRN 2996-92-1

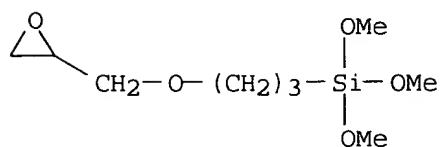
CMF C9 H14 O3 Si



CM 4

CRN 2530-83-8

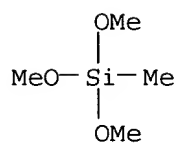
CMF C9 H20 O5 Si



CM 5

CRN 1185-55-3

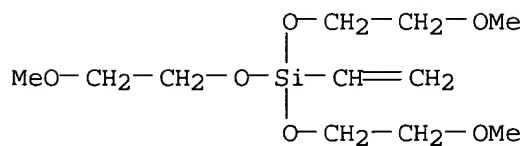
CMF C4 H12 O3 Si



CM 6

CRN 1067-53-4

CMF C11 H24 O6 Si

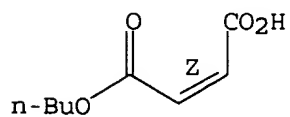


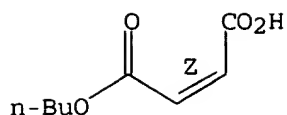
CM 7

CRN 925-21-3

CMF C8 H12 O4

Double bond geometry as shown.

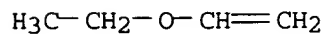




CM 8

CRN 109-92-2

CMF C4 H8 O



CM 9

CRN 108-05-4

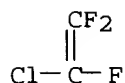
CMF C4 H6 O2



CM 10

CRN 79-38-9

CMF C2 Cl F3



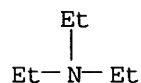
RN 234080-13-8 CAPLUS

CN 2-Butenedioic acid (2Z)-, monobutyl ester, polymer with chlorotrifluoroethene, ethenyl acetate, 6-ethenyl-6-(2-methoxyethoxy)-2,5,7,10-tetraoxa-6-silaundecane, ethoxyethene, trimethoxy[3-(oxiranylmethoxy)propyl]silane and trimethoxyphenylsilane, compd. with N,N-diethylethanamine (9CI) (CA INDEX NAME)

CM 1

CRN 121-44-8

CMF C6 H15 N



CM 2

CRN 234080-12-7

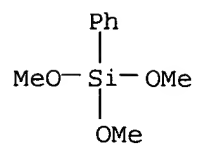
CMF (C11 H24 O6 Si . C9 H20 O5 Si . C9 H14 O3 Si . C8 H12 O4 . C4 H8 O . C4 H6 O2 . C2 Cl F3)x

CCI PMS

CM 3

CRN 2996-92-1

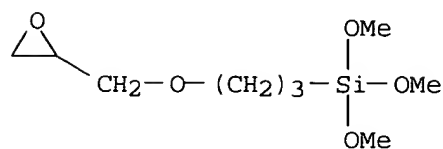
CMF C9 H14 O3 Si



CM 4

CRN 2530-83-8

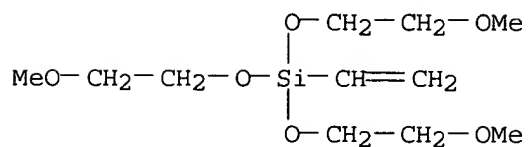
CMF C9 H20 O5 Si



CM 5

CRN 1067-53-4

CMF C11 H24 O6 Si

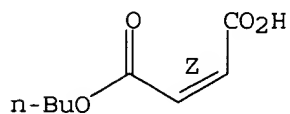


CM 6

CRN 925-21-3

CMF C8 H12 O4

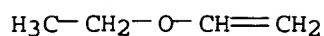
Double bond geometry as shown.



CM 7

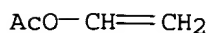
CRN 109-92-2

CMF C4 H8 O



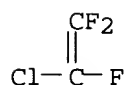
CM 8

CRN 108-05-4
CMF C4 H6 O2



CM 9

CRN 79-38-9
CMF C2 Cl F3



L11 ANSWER 13 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1999:481605 CAPLUS

DN 131:131340

TI Coating films with high gloss retention and pollution resistance

IN Kudou, Shinichi; Kinoshita, Koji; Ohoka, Masataka

PA Dainippon Ink and Chemicals, Inc., Japan

SO Jpn. Kokai Tokkyo Koho, 58 pp.

CODEN: JKXXAF

DT Patent

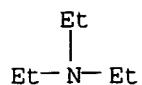
LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11209692	A2	19990803	JP 1998-11151	19980123
IT	234080-03-6P , Monobutyl maleate-vinyl acetate-ethyl vinyl ether-vinyltris(.beta.-methoxyethoxy)silane-chlorotrifluoroethylene-phenyltrimethoxysilane-methyltrimethoxysilane-3-glycidoxypentyltrimethoxysilane copolymer triethylamine salt 234080-13-8P , Monobutyl maleate-vinyl acetate-ethyl vinyl ether-vinyltris(.beta.-methoxyethoxy)silane-chlorotrifluoroethylene-phenyltrimethoxysilane-(3-glycidoxypentyl)trimethoxysilane copolymer triethylamine salt RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (coating films with high gloss retention and pollution resistance)				
RN	234080-03-6 CAPLUS				
CN	2-Butenedioic acid (2Z)-, monobutyl ester, polymer with chlorotrifluoroethene, ethenyl acetate, 6-ethenyl-6-(2-methoxyethoxy)-2,5,7,10-tetraoxa-6-silaundecane, ethoxyethene, trimethoxymethylsilane, trimethoxy[3-(oxiranylmethoxy)propyl]silane and trimethoxyphenylsilane, compd. with N,N-diethylethanamine (9CI) (CA INDEX NAME)				

CM 1

CRN 121-44-8
CMF C6 H15 N



CM 2

CRN 234080-02-5

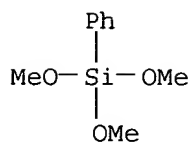
CMF (C11 H24 O6 Si . C9 H20 O5 Si . C9 H14 O3 Si . C8 H12 O4 . C4 H12 O3
Si . C4 H8 O . C4 H6 O2 . C2 Cl F3)x

CCI PMS

CM 3

CRN 2996-92-1

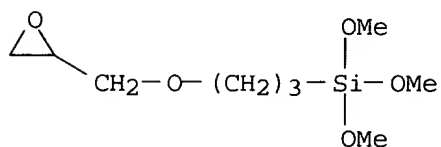
CMF C9 H14 O3 Si



CM 4

CRN 2530-83-8

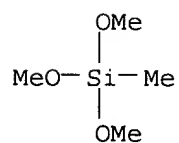
CMF C9 H20 O5 Si



CM 5

CRN 1185-55-3

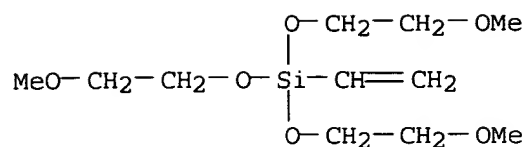
CMF C4 H12 O3 Si



CM 6

CRN 1067-53-4

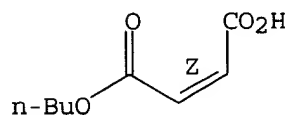
CMF C11 H24 O6 Si



CM 7

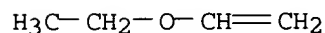
CRN 925-21-3
CMF C8 H12 O4

Double bond geometry as shown.



CM 8

CRN 109-92-2
CMF C4 H8 O



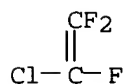
CM 9

CRN 108-05-4
CMF C4 H6 O2



CM 10

CRN 79-38-9
CMF C2 Cl F3

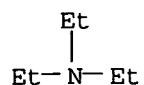


RN 234080-13-8 CAPLUS
CN 2-Butenedioic acid (2Z)-, monobutyl ester, polymer with chlorotrifluoroethene, ethenyl acetate, 6-ethenyl-6-(2-methoxyethoxy)-2,5,7,10-tetraoxa-6-silaundecane, ethoxyethene, trimethoxy[3-(oxiranylmethoxy)propyl]silane and trimethoxyphenylsilane, compd. with N,N-diethylethanamine (9CI) (CA INDEX NAME)

CM 1

CRN 121-44-8

CMF C6 H15 N



CM 2

CRN 234080-12-7

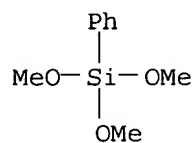
CMF (C11 H24 O6 Si . C9 H20 O5 Si . C9 H14 O3 Si . C8 H12 O4 . C4 H8 O . C4 H6 O2 . C2 Cl F3)x

CCI PMS

CM 3

CRN 2996-92-1

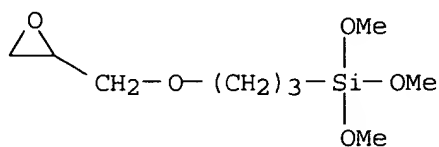
CMF C9 H14 O3 Si



CM 4

CRN 2530-83-8

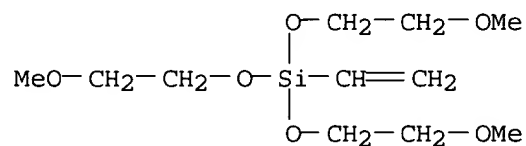
CMF C9 H20 O5 Si



CM 5

CRN 1067-53-4

CMF C11 H24 O6 Si

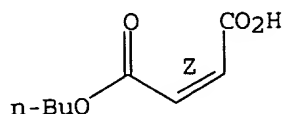


CM 6

CRN 925-21-3

CMF C8 H12 O4

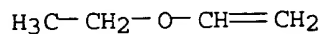
Double bond geometry as shown.



CM 7

CRN 109-92-2

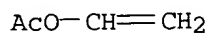
CMF C4 H8 O



CM 8

CRN 108-05-4

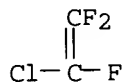
CMF C4 H6 O2



CM 9

CRN 79-38-9

CMF C2 Cl F3



L11 ANSWER 14 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1999:481539 CAPLUS

DN 131:145843

TI Manufacture of room-temperature-curable organo polysiloxane compositions for sealants

IN Miyake, Masatoshi; Suzuki, Kazuyuki; Teshigahara, Mamoru; Kimura, Tsuneo

PA Shin-Etsu Chemical Industry Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11209621	A2	19990803	JP 1998-32145	19980129
	US 6214930	B1	20010410	US 1999-237799	19990127
	EP 933398	A2	19990804	EP 1999-300623	19990128
	EP 933398	A3	20001011		

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO

PRAI JP 1998-32145 A 19980129

IT 235764-03-1P, Dimethylsilanediol-.gamma.-

glycidoxypropyltrimethoxysilane-methylsilanetriol-vinyltrimethoxysilane copolymer

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(rubber; room-temp.-curable silicone rubber compns. with good sagging prevention and discharge stability)

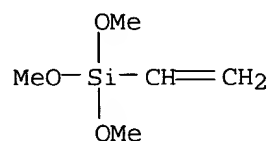
RN 235764-03-1 CAPLUS

CN Silanetriol, methyl-, polymer with dimethylsilanediol, ethenyltrimethoxysilane and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 2768-02-7

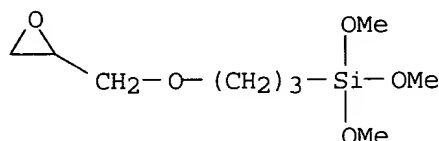
CMF C5 H12 O3 Si



CM 2

CRN 2530-83-8

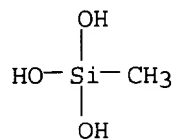
CMF C9 H20 O5 Si



CM 3

CRN 2445-53-6

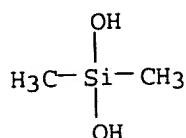
CMF C H6 O3 Si



CM 4

CRN 1066-42-8

CMF C2 H8 O2 Si



L11 ANSWER 15 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1999:481405 CAPLUS

DN 131:158326

TI Waterborne resins, their manufacture and waterborne curable compositions containing them

IN Kudo, Shinichi; Tomita, Hidetoshi; Kinoshita, Koji; Ooka, Masataka

PA Dainippon Ink and Chemicals, Inc., Japan

SO Jpn. Kokai Tokkyo Koho, 46 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

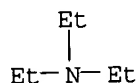
FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11209473	A2	19990803	JP 1998-13075	19980126
IT	234110-94-2P , Chlorotrifluoroethylene-cyclohexyltrimethoxysilane-ethyl vinyl ether-3-glycidoxypentyltrimethoxysilane-methyltrimethoxysilane-monobutyl maleate-vinyl acetate-vinyltris(2-methoxyethoxy)silane copolymer triethylamine salt RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (coatings; storage-stable waterborne siloxane compns. and use in coatings and sealants)				
RN	234110-94-2 CAPLUS				
CN	2-Butenedioic acid (2Z)-, monobutyl ester, polymer with chlorotrifluoroethylene, cyclohexyltrimethoxysilane, ethenyl acetate, 6-ethenyl-6-(2-methoxyethoxy)-2,5,7,10-tetraoxa-6-silaundecane, ethoxyethene, trimethoxymethylsilane and trimethoxy[3-(oxiranylmethoxy)propyl]silane, compd. with N,N-diethylethanamine (9CI) (CA INDEX NAME)				

CM 1

CRN 121-44-8

CMF C6 H15 N



CM 2

CRN 234110-93-1

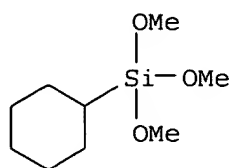
CMF (C11 H24 O6 Si . C9 H20 O5 Si . C9 H20 O3 Si . C8 H12 O4 . C4 H12 O3 Si . C4 H8 O . C4 H6 O2 . C2 Cl F3)x

CCI PMS

CM 3

CRN 17865-54-2

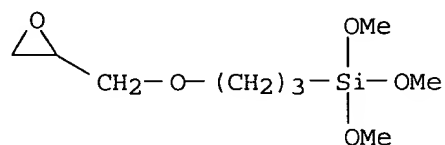
CMF C9 H20 O3 Si



CM 4

CRN 2530-83-8

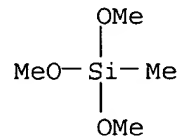
CMF C9 H20 O5 Si



CM 5

CRN 1185-55-3

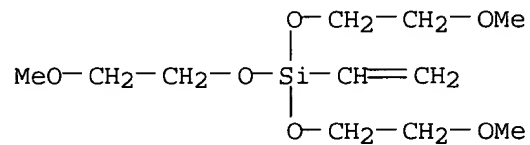
CMF C4 H12 O3 Si



CM 6

CRN 1067-53-4

CMF C11 H24 O6 Si

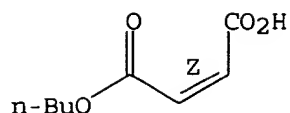


CM 7

CRN 925-21-3

CMF C8 H12 O4

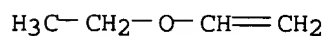
Double bond geometry as shown.



CM 8

CRN 109-92-2

CMF C4 H8 O



CM 9

CRN 108-05-4

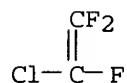
CMF C4 H6 O2



CM 10

CRN 79-38-9

CMF C2 Cl F3



L11 ANSWER 16 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1999:409343 CAPLUS

DN 131:60158

TI Inorganic-organic composite aqueous coating compositions

IN Kito, Koichi; Saegusa, Kazumasa

PA Dainippon Toryo Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11172200	A2	19990629	JP 1997-342688	19971212

IT **227451-42-5P**

RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (inorg.-org. composite aq. coating compns. contg. fluoropolymers and acrylic polymers having hydrolyzable silyl groups and alkoxy silane condensates)

RN 227451-42-5 CAPLUS

CN 10-Undecenoic acid, polymer with chlorotrifluoroethene, ethenyl butanoate, ethenyl 2,2-dimethylpropanoate, ethenyl neononanoate, ethenyltrimethoxysilane, trimethoxymethylsilane and trimethoxy[3-

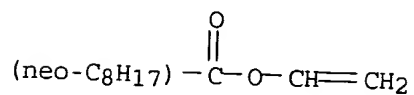
(oxiranylmethoxy)propylsilane (9CI) (CA INDEX NAME)

CM 1

CRN 54423-67-5

CMF C11 H20 O2

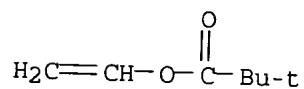
CCI IDS



CM 2

CRN 3377-92-2

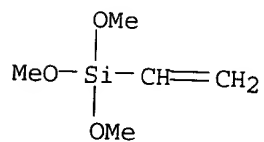
CMF C7 H12 O2



CM 3

CRN 2768-02-7

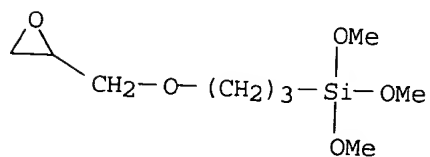
CMF C5 H12 O3 Si



CM 4

CRN 2530-83-8

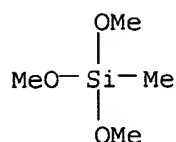
CMF C9 H20 O5 Si



CM 5

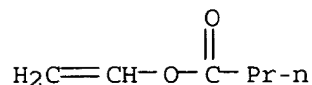
CRN 1185-55-3

CMF C4 H12 O3 Si



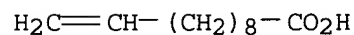
CM 6

CRN 123-20-6
CMF C6 H10 O2



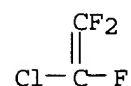
CM 7

CRN 112-38-9
CMF C11 H20 O2



CM 8

CRN 79-38-9
CMF C2 C1 F3



L11 ANSWER 17 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1999:319021 CAPLUS

DN 131:6638

TI Aqueous compositions for crack-resistant hard coats for plastic lenses, their manufacture and laminates

IN Miyashita, Kazunori; Kinoshita, Atsushi

PA Seiko Epson Corp., Japan

SO Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 2

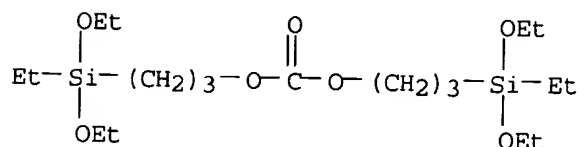
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	----	-----	-----	-----
PI	JP 11130982	A2	19990518	JP 1998-153421	19980602
PRAI	JP 1997-236321		19970901		
IT	225663-60-5P				

RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (oxide (composite)-contg. polysiloxane coatings with crack resistance for plastic lenses)

RN 225663-60-5 CAPLUS
 CN Propanol, 1,3(or 2,3)-bis(oxiranylmethoxy)-, polymer with
 bis[3-(diethoxyethylsilyl)propyl] carbonate, ethenyltrimethoxysilane and
 trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

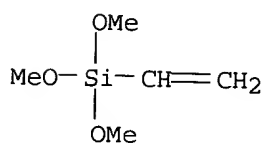
CM 1

CRN 225663-58-1
 CMF C19 H42 O7 Si2



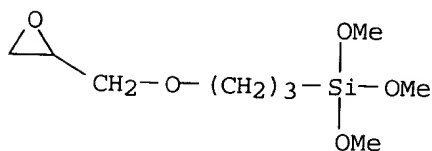
CM 2

CRN 2768-02-7
 CMF C5 H12 O3 Si



CM 3

CRN 2530-83-8
 CMF C9 H20 O5 Si

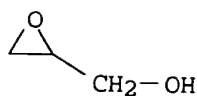


CM 4

CRN 27043-36-3
 CMF C9 H16 O5
 CCI IDS

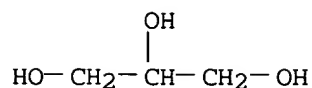
CM 5

CRN 556-52-5
 CMF C3 H6 O2



CM 6

CRN 56-81-5
CMF C3 H8 O3



L11 ANSWER 18 OF 34 CAPLUS COPYRIGHT 2002 ACS
AN 1998:650462 CAPLUS
DN 129:303751
TI Compositions for fluoropolymer coatings
IN Iida, Akihito; Marumoto, Etsuzo; Maruyama, Yasuomi; Inukai, Hiroshi
PA Toa Gosei Chemical Industry Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

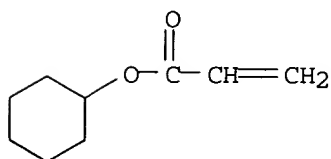
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 10265731	A2	19981006	JP 1997-88664	19970325
IT	214559-39-4P 214559-40-7P 214559-41-8P 214559-42-9P 214559-43-0P				

RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(cured enamel film; fluoropolymers in aliph. hydrocarbon compns. for soil/solvent-resistant enamel coatings)

RN 214559-39-4 CAPLUS
CN 2-Propenoic acid, cyclohexyl ester, polymer with chlorotrifluoroethene, ethenyltrimethoxysilane, silicic acid ethyl ester and trimethoxy[3-(oxiranylethoxy)propyl]silane (9CI) (CA INDEX NAME)

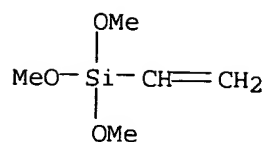
CM 1

CRN 3066-71-5
CMF C9 H14 O2



CM 2

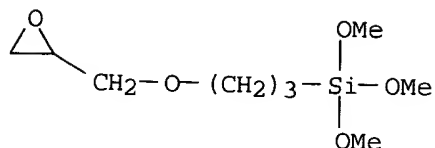
CRN 2768-02-7
CMF C5 H12 O3 Si



CM 3

CRN 2530-83-8

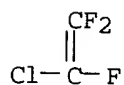
CMF C9 H20 O5 Si



CM 4

CRN 79-38-9

CMF C2 Cl F3



CM 5

CRN 11099-06-2

CMF C2 H6 O . x Unspecified

CM 6

CRN 1343-98-2

CMF Unspecified

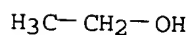
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 7

CRN 64-17-5

CMF C2 H6 O

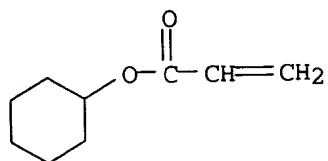


RN 214559-40-7 CAPLUS

CN 2-Propenoic acid, butyl ester, polymer with chlorotrifluoroethene, cyclohexyl 2-propenoate, ethenyltrimethoxysilane, silicic acid ethyl ester and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

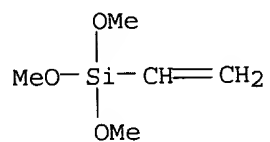
CM 1

CRN 3066-71-5
CMF C9 H14 O2



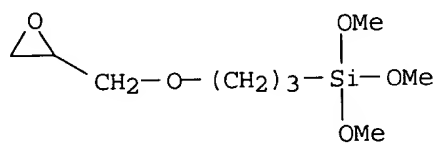
CM 2

CRN 2768-02-7
CMF C5 H12 O3 Si



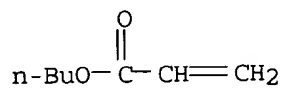
CM 3

CRN 2530-83-8
CMF C9 H20 O5 Si



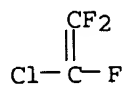
CM 4

CRN 141-32-2
CMF C7 H12 O2



CM 5

CRN 79-38-9
CMF C2 Cl F3



CM 6

CRN 11099-06-2

CMF C2 H6 O . x Unspecified

CM 7

CRN 1343-98-2

CMF Unspecified

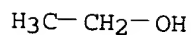
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 8

CRN 64-17-5

CMF C2 H6 O



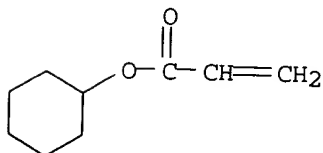
RN 214559-41-8 CAPLUS

CN 2-Propenoic acid, cyclohexyl ester, polymer with chlorotrifluoroethene, ethenyltrimethoxysilane, 2-methylpropyl 2-propenoate, silicic acid ethyl ester and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 3066-71-5

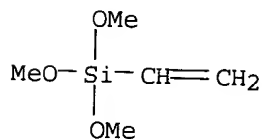
CMF C9 H14 O2



CM 2

CRN 2768-02-7

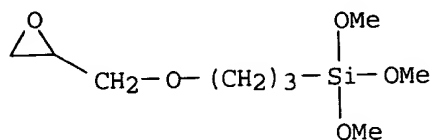
CMF C5 H12 O3 Si



CM 3

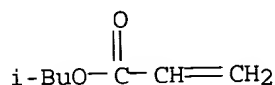
CRN 2530-83-8

CMF C9 H20 O5 Si



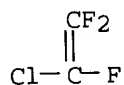
CM 4

CRN 106-63-8
CMF C7 H12 O2



CM 5

CRN 79-38-9
CMF C2 Cl F3



CM 6

CRN 11099-06-2
CMF C2 H6 O . x Unspecified

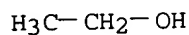
CM 7

CRN 1343-98-2
CMF Unspecified
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 8

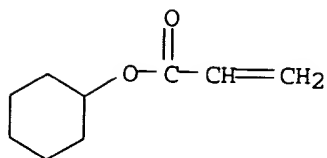
CRN 64-17-5
CMF C2 H6 O



RN 214559-42-9 CAPLUS
CN 2-Propenoic acid, butyl ester, polymer with chlorotrifluoroethene,
cyclohexyl 2-propenoate, 1,1-dimethylethyl 2-propenoate,
ethenyltrimethoxysilane, silicic acid ethyl ester and trimethoxy[3-
(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

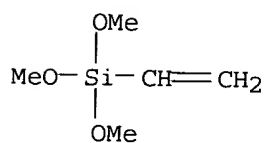
CM 1

CRN 3066-71-5
CMF C9 H14 O2



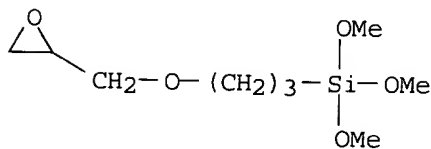
CM 2

CRN 2768-02-7
CMF C5 H12 O3 Si



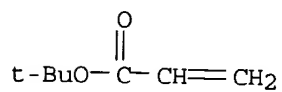
CM 3

CRN 2530-83-8
CMF C9 H20 O5 Si



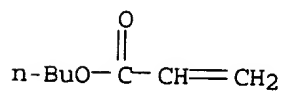
CM 4

CRN 1663-39-4
CMF C7 H12 O2



CM 5

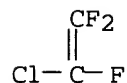
CRN 141-32-2
CMF C7 H12 O2



CM 6

CRN 79-38-9

CMF C2 Cl F3



CM 7

CRN 11099-06-2

CMF C2 H6 O . x Unspecified

CM 8

CRN 1343-98-2

CMF Unspecified

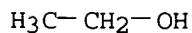
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 9

CRN 64-17-5

CMF C2 H6 O



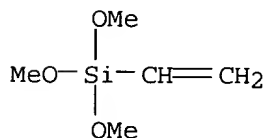
RN 214559-43-0 CAPLUS

CN Silicic acid, ethyl ester, polymer with chlorotrifluoroethene, 1-(ethenyloxy)butane, (ethenyloxy)cyclohexane, ethenyltrimethoxysilane and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 2768-02-7

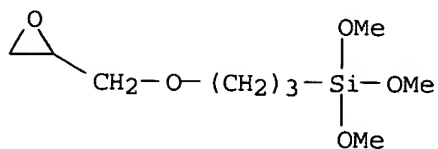
CMF C5 H12 O3 Si



CM 2

CRN 2530-83-8

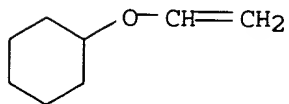
CMF C9 H20 O5 Si



CM 3

CRN 2182-55-0

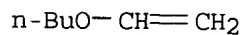
CMF C8 H14 O



CM 4

CRN 111-34-2

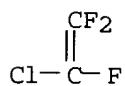
CMF C6 H12 O



CM 5

CRN 79-38-9

CMF C2 Cl F3



CM 6

CRN 11099-06-2

CMF C2 H6 O . x Unspecified

CM 7

CRN 1343-98-2

CMF Unspecified

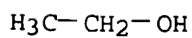
CCI MAN

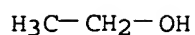
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 8

CRN 64-17-5

CMF C2 H6 O





L11 ANSWER 19 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1998:509159 CAPLUS

DN 129:168124

TI Laser-imageable recording material and printing plate produced therefrom for waterless offset printing

IN Grabley, Fritz-Feo; Gries, Willi-Kurt; Schlosser, Hans-Joachim

PA Agfa-Gevaert Naamloze Vennootschap, Belg.

SO PCT Int. Appl., 21 pp.

CODEN: PIXXD2

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9831550	A1	19980723	WO 1998-EP146	19980108
	W: BR, JP, KR				
	RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
	EP 952926	A1	19991103	EP 1998-904059	19980108
	EP 952926	B1	20020123		
	R: BE, DE, FR, GB, IT				
	JP 2001508001	T2	20010619	JP 1998-532304	19980108
PRAI	EP 1997-200144	A	19970117		
	WO 1998-EP146	W	19980108		

IT 210993-79-6, HF 86

RL: DEV (Device component use); TEM (Technical or engineered material use); USES (Uses)

(HF 86; laser recording materials for waterless offset printing plate prepn. contg.)

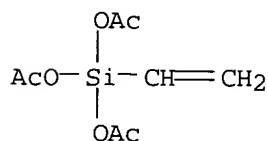
RN 210993-79-6 CAPLUS

CN Silanetriol, ethenyl-, triacetate, mixt. with trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 4130-08-9

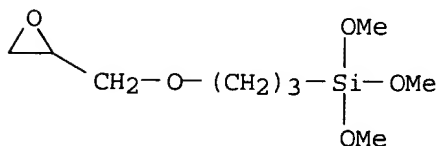
CMF C8 H12 O6 Si



CM 2

CRN 2530-83-8

CMF C9 H20 O5 Si



L11 ANSWER 20 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1998:358415 CAPLUS

DN 129:123113

TI Inorganic-organic proton conductors based on alkylsulfone functionalities and their patterning by photoinduced methods

AU Depre, Laurent; Kappel, Jurgen; Popall, Michael

CS Fraunhofer-Inst. Silicatforschung, Wurzburg, D-97082, Germany

SO Electrochimica Acta (1998), 43(10-11), 1301-1306

CODEN: ELCAAV; ISSN: 0013-4686

PB Elsevier Science Ltd.

DT Journal

LA English

IT 210160-22-8P

RL: PEP (Physical, engineering or chemical process); PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)

(prepn. of inorg.-org. proton conductors from trimethoxysilanes and tetraethoxysilane by sol-gel processing and their patterning by photoinduced methods)

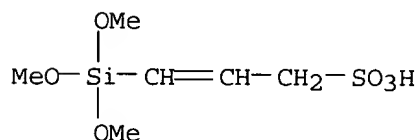
RN 210160-22-8 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(trimethoxysilyl)propyl ester, polymer with silicic acid (H₄SiO₄) tetraethyl ester, trimethoxy[3-(oxiranylmethoxy)propyl]silane and 3-(trimethoxysilyl)-2-propene-1-sulfonic acid (9CI) (CA INDEX NAME)

CM 1

CRN 210160-21-7

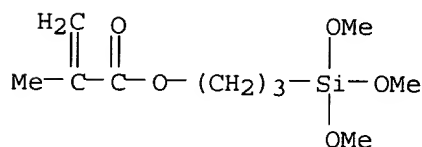
CMF C6 H14 O6 S Si



CM 2

CRN 2530-85-0

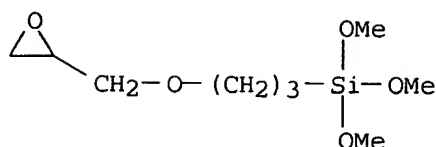
CMF C10 H20 O5 Si



CM 3

CRN 2530-83-8

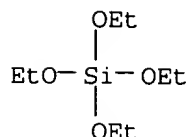
CMF C9 H20 O5 Si



CM 4

CRN 78-10-4

CMF C8 H20 O4 Si



L11 ANSWER 21 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1998:202626 CAPLUS

DN 128:288304

TI Release layer for electrophotographic photoreceptor

IN Lehman, Gaye K.; Jalbert, Claire A.; Woo, Edward J.; Bretscher, Kathryn R.; Baker, James A.; Berens, Mark C.

PA Minnesota Mining and Manufacturing Company, USA

SO U.S., 8 pp.

CODEN: USXXAM

DT Patent

LA English

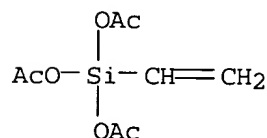
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 5733698	A	19980331	US 1996-724073	19960930
IT	69882-18-4 , Syloff 297 RL: DEV (Device component use); TEM (Technical or engineered material use); USES (Uses) (electrophotog. photoreceptors with swellable polymer release layers contg.)				
RN	69882-18-4 CAPLUS				
CN	Silanetriol, ethenyl-, triacetate, polymer with trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)				

CM 1

CRN 4130-08-9

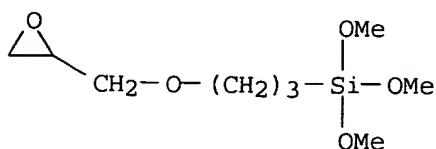
CMF C8 H12 O6 Si



CM 2

CRN 2530-83-8

CMF C9 H20 O5 Si



L11 ANSWER 22 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1997:351073 CAPLUS

DN 126:323306

TI Release layer for electrophotographic photoreceptor

IN Lehman, Gaye K.; Woo, Edward J.; Jalbert, Claire A.; Bretscher, Kathryn R.; Baker, James A.; Berens, Mark C.

PA Imation Corp., USA

SO PCT Int. Appl., 30 pp.

CODEN: PIXXD2

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9712282	A1	19970403	WO 1996-US15520	19960930
	W: JP, KR				
	RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
	EP 852744	A1	19980715	EP 1996-933933	19960930
	R: DE, FR, GB, IT				
	JP 11515112	T2	19991221	JP 1996-513674	19960930
PRAI	US 1995-4614P	P	19950929		
	WO 1996-US15520	W	19960930		

IT 69882-18-4

RL: TEM (Technical or engineered material use); USES (Uses)
(Syl-off 297; electrophotog. photoreceptors with liq. developer release layers contg.)

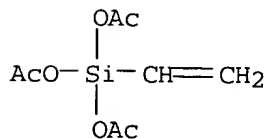
RN 69882-18-4 CAPLUS

CN Silanetriol, ethenyl-, triacetate, polymer with trimethoxy[3-(oxiranylethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 4130-08-9

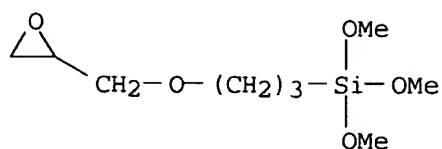
CMF C8 H12 O6 Si



CM 2

CRN 2530-83-8

CMF C9 H20 O5 Si



L11 ANSWER 23 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1996:579780 CAPLUS

DN 125:223553

TI Noncombustible polycarbonate compositions resistant to dripping in burning

IN Nodera, Akio; Takarada, Mitsuhiro; Matsumura, Kazuyuki; Kizaki, Hiroaki

PA Idemitsu Petrochemical Co, Japan; Shinetsu Chem Ind Co

SO Jpn. Kokai Tokkyo Koho, 9 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

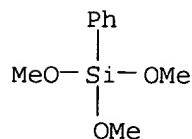
FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08176425	A2	19960709	JP 1994-319691	19941222
	JP 3163596	B2	20010508		
IT	181258-35-5P				
	RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)				
	(noncombustible polycarbonate compns. resistant to dripping in burning)				
RN	181258-35-5 CAPLUS				
CN	Silane, ethenyltrimethoxy-, polymer with trimethoxy[3-(oxiranylmethoxy)propyl]silane and trimethoxyphenylsilane (9CI) (CA INDEX NAME)				

CM 1

CRN 2996-92-1

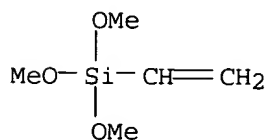
CMF C9 H14 O3 Si



CM 2

CRN 2768-02-7

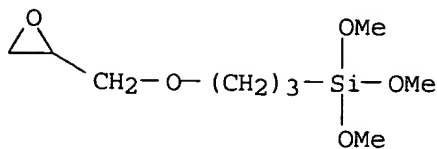
CMF C5 H12 O3 Si



CM 3

CRN 2530-83-8

CMF C9 H20 O5 Si



L11 ANSWER 24 OF 34 CAPLUS COPYRIGHT 2002 ACS
AN 1996:513098 CAPLUS
DN 125:144691
TI Adhesive compositions curable at room temperature
IN Murayama, Yukihiro; Ppanda, Junichi
PA Sekisui Chemical Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 4 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08127712	A2	19960521	JP 1994-269404	19941102

IT 180211-93-2P

RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(rubber; adhesive compns. curable at room temp.)

RN 180211-93-2 CAPLUS

CN 2-Propanol, 1-[bis[2-[(1,3-dimethylbutylidene)amino]ethyl]amino]-3-butoxy-, polymer with ethenyltrimethoxysilane, Kaneka Silyl MAX 447 and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 179987-19-0

CMF Unspecified

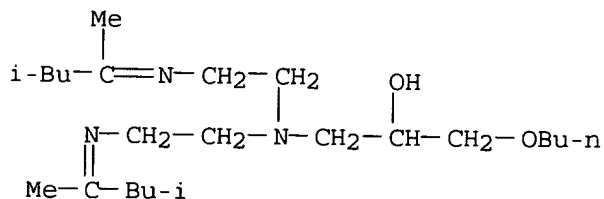
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 37187-55-6

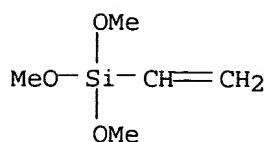
CMF C23 H47 N3 O2



CM 3

CRN 2768-02-7

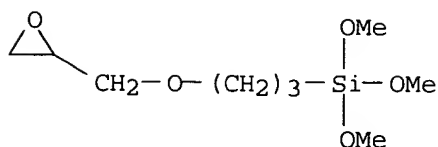
CMF C5 H12 O3 Si



CM 4

CRN 2530-83-8

CMF C9 H20 O5 Si



L11 ANSWER 25 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1995:969466 CAPLUS

DN 123:343665

TI Acrylic siloxane primer compositions used in injection molding process

IN Tanuma, Yoichiro

PA Toshiba Silicone, Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 07207231	A2	19950808	JP 1994-5888	19940124
IT	171183-34-9P				

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(acrylic siloxane primers for manuf. of plastic-covered elec. wires inserted in rubber moldings)

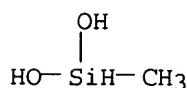
RN 171183-34-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(trimethoxysilyl)propyl ester, polymer with dimethylsilanediol, ethenyltriethoxysilane, methylsilanediol and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

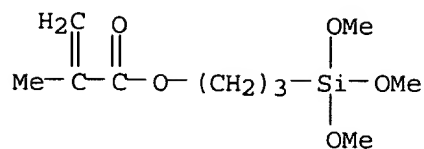
CRN 43641-90-3

CMF C H6 O2 Si



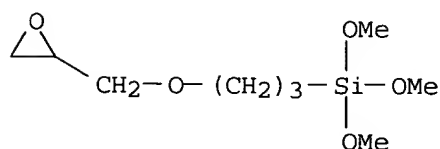
CM 2

CRN 2530-85-0
CMF C10 H20 O5 Si



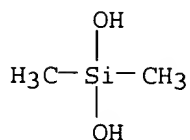
CM 3

CRN 2530-83-8
CMF C9 H20 O5 Si



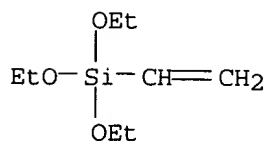
CM 4

CRN 1066-42-8
CMF C2 H8 O2 Si



CM 5

CRN 78-08-0
CMF C8 H18 O3 Si



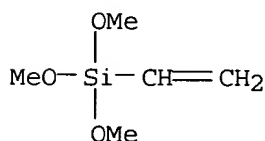
L11 ANSWER 26 OF 34 CAPLUS COPYRIGHT 2002 ACS
AN 1995:632162 CAPLUS
DN 123:12022
TI Optical materials having reflection-preventing layers and manufacture thereof
IN Takahashi, Kenji; Uehara, Masaru; Kato, Hirotsugu
PA Sumitomo Osaka Semento Kk, Japan
SO Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF

DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 07048527	A2	19950221	JP 1993-196533	19930806
IT	164065-58-1P				
RL:	IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (reflection-preventing coatings contg. siloxanes and silica on optical material)				
RN	164065-58-1	CAPLUS			
CN	Silane, ethenyltrimethoxy-, polymer with trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)				

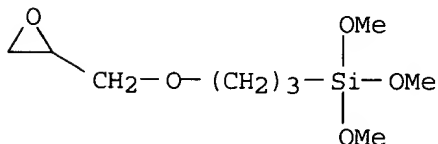
CM 1

CRN 2768-02-7
CMF C5 H12 O3 Si



CM 2

CRN 2530-83-8
CMF C9 H20 O5 Si



L11 ANSWER 27 OF 34 CAPLUS COPYRIGHT 2002 ACS
AN 1995:578472 CAPLUS
DN 122:316348
TI Manufacture of pressure-sensitive adhesive tapes
IN Fisher, Dennis K.; Eder, Stephen J.; Briddell, Brian J.
PA Adco Products, Inc., USA
SO Eur. Pat. Appl., 24 pp.
CODEN: EPXXDW

DT Patent
LA English

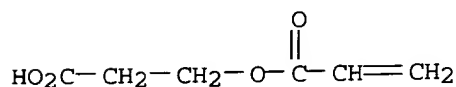
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 625527	A1	19941123	EP 1994-303505	19940517
	EP 625527	B1	20000308		
	R: DE, GB				
	CA 2123775	AA	19941118	CA 1994-2123775	19940517
	WO 9426423	A1	19941124	WO 1994-US4817	19940517
	W: JP				
	JP 08508063	T2	19960827	JP 1994-525500	19940517

PRAI US 1993-61809 19930517
 WO 1994-US4817 19940517
 IT 163421-45-2P, .beta.-Carboxyethyl acrylate-2-ethylhexyl
 acrylate-.gamma.-glycidyloxypropyltrimethoxysilane-vinyltrimethoxysilane
 copolymer
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material
 use); PREP (Preparation); USES (Uses)
 (adhesive; pressure-sensitive adhesive tapes with good adhesion to
 silane-modified acrylic/melamine resin paints)
 RN 163421-45-2 CAPLUS
 CN 2-Propenoic acid, 2-carboxyethyl ester, polymer with
 ethenyltrimethoxysilane, 2-ethylhexyl 2-propenoate and
 trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7

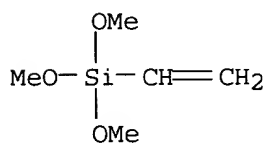
CMF C6 H8 O4



CM 2

CRN 2768-02-7

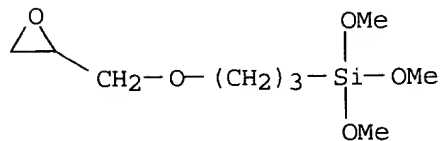
CMF C5 H12 O3 Si



CM 3

CRN 2530-83-8

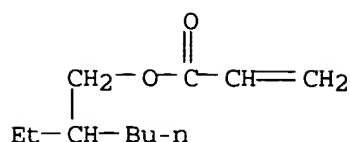
CMF C9 H20 O5 Si



CM 4

CRN 103-11-7

CMF C11 H20 O2



L11 ANSWER 28 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1994:109600 CAPLUS

DN 120:109600

TI Hemiacetal or hemiketal ester-protected functional group-containing vinyl polymers for coatings

IN Azuma, Ichiro; Iwamura, Goro; Takezawa, Shoichiro; Oooka, Masataka; Yamamura, Kazuo

PA Dainippon Ink & Chemicals, Japan

SO Jpn. Kokai Tokkyo Koho, 30 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05186739	A2	19930727	JP 1992-3841	19920113
IT	152330-14-8				

RL: TEM (Technical or engineered material use); USES (Uses)
(coatings, from hemiacetal- or hemiketal-blocked acrylic polymers, acid- and scratch-resistant)

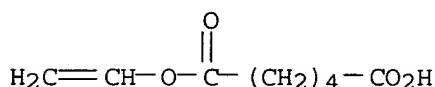
RN 152330-14-8 CAPLUS

CN Hexanedioic acid, monoethenyl ester, polymer with chlorotrifluoroethene, ethenyltrimethoxysilane, ethoxyethene and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 5238-38-0

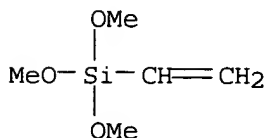
CMF C8 H12 O4



CM 2

CRN 2768-02-7

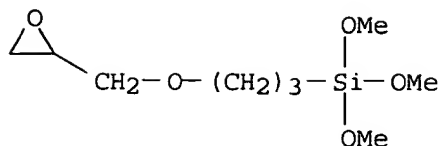
CMF C5 H12 O3 Si



CM 3

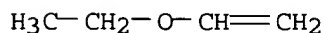
CRN 2530-83-8

CMF C9 H20 O5 Si



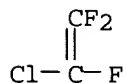
CM 4

CRN 109-92-2
CMF C4 H8 O



CM 5

CRN 79-38-9
CMF C2 Cl F3



L11 ANSWER 29 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1993:409825 CAPLUS

DN 119:9825

TI Crosslinkable polymeric composition

IN Lien, Klaus; Reid, William Bain

PA BP Chemicals Ltd., UK

SO PCT Int. Appl., 31 pp.

CODEN: PIXXD2

DT Patent

LA English

FAN.CNT 1

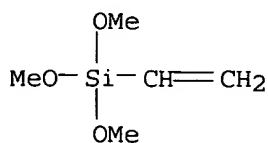
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9221721	A1	19921210	WO 1992-GB981	19920601
	W: AU, FI, JP, KR, NO				
	RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LU, MC, NL, SE				
	AU 9218860	A1	19930108	AU 1992-18860	19920601
	AU 654361	B2	19941103		
	EP 541747	A1	19930519	EP 1992-910727	19920601
	EP 541747	B1	19990825		
	R: BE, CH, DE, DK, FR, GB, IT, LI, NL, SE				
	JP 06506257	T2	19940714	JP 1992-509868	19920601
	JP 3187048	B2	20010711		
	NO 9300299	A	19930128	NO 1993-299	19930128
PRAI	GB 1991-11754	A	19910531		
	GB 1991-11755	A	19910531		
	WO 1992-GB981	A	19920601		
IT	148209-85-2P				
	RL: PREP (Preparation)				
	(prepn. of cured, for cable insulation)				
RN	148209-85-2 CAPLUS				

CN Silane, ethenyltrimethoxy-, polymer with ethene and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 2768-02-7

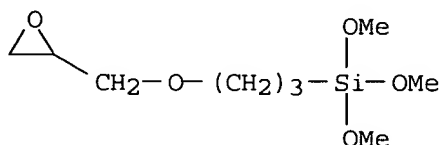
CMF C5 H12 O3 Si



CM 2

CRN 2530-83-8

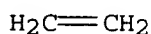
CMF C9 H20 O5 Si



CM 3

CRN 74-85-1

CMF C2 H4



L11 ANSWER 30 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1981:471055 CAPLUS

DN 95:71055

TI Driographic printing plate

IN Ball, Alan

PA Minnesota Mining and Mfg. Co., USA

SO U.S., 10 pp.

CODEN: USXXAM

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 4225663	A	19800930	US 1974-500385	19740826

IT 69882-18-4

RL: USES (Uses)

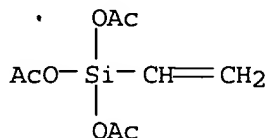
(driog. printing plates with ink-repellent layers contg.)

RN 69882-18-4 CAPLUS

CN Silanetriol, ethenyl-, triacetate, polymer with trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

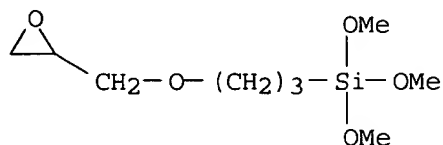
CM 1

CRN 4130-08-9
CMF C8 H12 O6 Si



CM 2

CRN 2530-83-8
CMF C9 H20 O5 Si



L11 ANSWER 31 OF 34 CAPLUS COPYRIGHT 2002 ACS

AN 1981:463890 CAPLUS

DN 95:63890

TI Hardenable coating agent and mar-resistant coatings on plastics

IN Jaeckel, Klaus Peter; Heil, Guenter; Spoor, Herbert

PA BASF A.-G. , Fed. Rep. Ger.

SO Ger. Offen., 19 pp.

CODEN: GWXXBX

DT Patent

LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 2946474	A1	19810527	DE 1979-2946474	19791117
	CA 1142682	A1	19830308	CA 1980-362963	19801022
	EP 29929	A1	19810610	EP 1980-106810	19801105
	EP 29929	B1	19820721		
	R: AT, BE, CH, DE, FR, GB, IT, LU, NL, SE				
	JP 56076469	A2	19810624	JP 1980-154719	19801105
	US 4336309	A	19820622	US 1980-204539	19801106
PRAI	DE 1979-2946474		19791117		

IT 78538-03-1 78591-13-6

RL: USES (Uses)

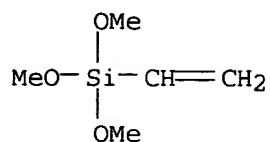
(coating materials, scratch-resistant, for plastics)

RN 78538-03-1 CAPLUS

CN 2-Propenoic acid, 2-hydroxyethyl ester, polymer with dibutoxydimethylsilane, ethenyltrimethoxysilane and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

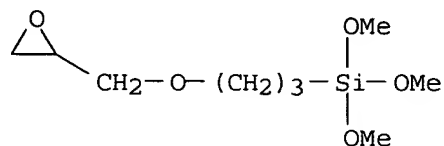
CRN 2768-02-7
CMF C5 H12 O3 Si



CM 2

CRN 2530-83-8

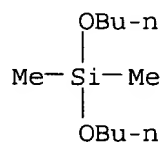
CMF C9 H20 O5 Si



CM 3

CRN 1591-02-2

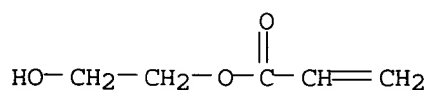
CMF C10 H24 O2 Si



CM 4

CRN 818-61-1

CMF C5 H8 O3



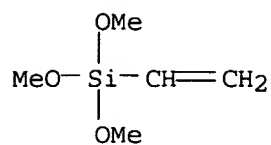
RN 78591-13-6 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(trimethoxysilyl)propyl ester, polymer with dibutoxydimethylsilane, ethenyltrimethoxysilane, 2-hydroxyethyl 2-propenoate and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

CM 1

CRN 2768-02-7

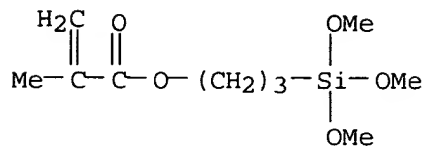
CMF C5 H12 O3 Si



CM 2

CRN 2530-85-0

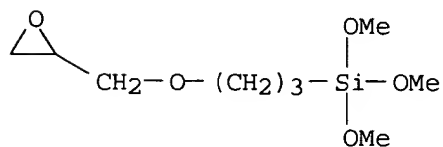
CMF C10 H20 O5 Si



CM 3

CRN 2530-83-8

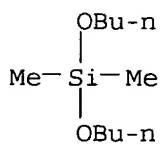
CMF C9 H20 O5 Si



CM 4

CRN 1591-02-2

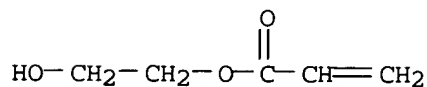
CMF C10 H24 O2 Si



CM 5

CRN 818-61-1

CMF C5 H8 O3



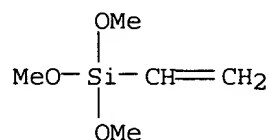
AN 1979:594786 CAPLUS
 DN 91:194786
 TI Curable resin compositions
 IN Kaetsu, Isao; Kumakura, Minoru; Yoshida, Masaru; Shimaoka, Goro; Koda, Hiroyuki; Taniyama, Susumu
 PA Japan Atomic Energy Research Institute, Japan; Mitsubishi Gas Chemical Co., Inc.
 SO Jpn. Kokai Tokkyo Koho, 15 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 54081400	A2	19790628	JP 1977-123078	19771014
	JP 61008103	B4	19860312		

IT **71878-04-1**
 RL: TEM (Technical or engineered material use); USES (Uses)
 (coatings, abrasion-resistant, for polycarbonates)
 RN 71878-04-1 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 3-(trimethoxysilyl)propyl ester, polymer with ethenyltrimethoxysilane, [(2-propenyloxy)methyl]oxirane and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

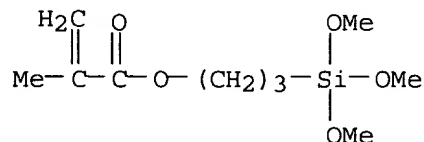
CM 1

CRN 2768-02-7
 CMF C5 H12 O3 Si



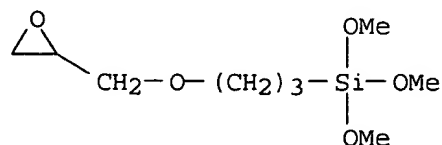
CM 2

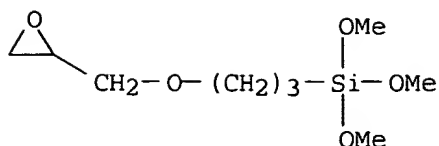
CRN 2530-85-0
 CMF C10 H20 O5 Si



CM 3

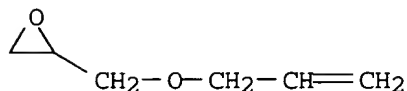
CRN 2530-83-8
 CMF C9 H20 O5 Si





CM 4

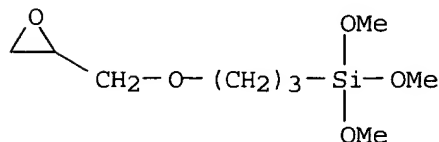
CRN 106-92-3
CMF C6 H10 O2



L11 ANSWER 33 OF 34 CAPLUS COPYRIGHT 2002 ACS
AN 1978:192850 CAPLUS
DN 88:192850
TI New coating materials prepared by radiation-induced polymerization. I.
Mar-resistant coating composition and properties
AU Okubo, H.; Kato, M.; Yoshida, M.; Ito, A.; Kaetsu, I.
CS Takasaki Radiat. Chem. Res. Establ., JAERI, Takasaki, Japan
SO J. Appl. Polym. Sci. (1978), 22(2), 487-96
CODEN: JAPNAB; ISSN: 0021-8995
DT Journal
LA English
IT **66451-47-6 66451-48-7**
RL: TEM (Technical or engineered material use); USES (Uses)
(coatings, mar-resistant and transparent, for org. glasses)
RN 66451-47-6 CAPLUS
CN Silane, ethenyltriethoxy-, polymer with trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

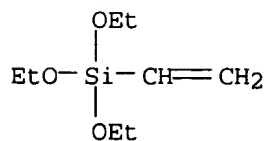
CM 1

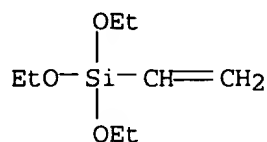
CRN 2530-83-8
CMF C9 H20 O5 Si



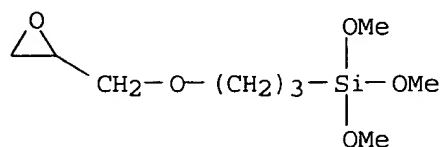
CM 2

CRN 78-08-0
CMF C8 H18 O3 Si

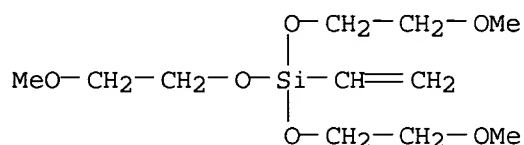




RN 66451-48-7 CAPLUS
 CN 2,5,7,10-Tetraoxa-6-silaundecane, 6-ethenyl-6-(2-methoxyethoxy)-, polymer with trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)
 CM 1
 CRN 2530-83-8
 CMF C9 H20 O5 Si



CM 2
 CRN 1067-53-4
 CMF C11 H24 O6 Si



L11 ANSWER 34 OF 34 CAPLUS COPYRIGHT 2002 ACS
 AN 1977:440397 CAPLUS
 DN 87:40397
 TI Transparent casting polymers
 IN Yoshida, Masaru; Kumakura, Minoru; Kaetsu, Isao
 PA Japan Atomic Energy Research Institute, Japan
 SO Japan. Kokai, 10 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 52037997	A2	19770324	JP 1975-113438	19750919
	JP 59010373	B4	19840308		

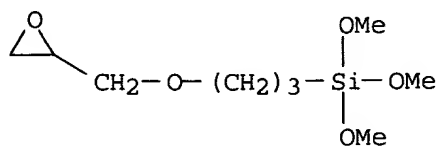
IT 63101-21-3

RL: USES (Uses)
 (transparent)

RN 63101-21-3 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 6-ethenyl-6-(2-methoxyethoxy)-2,5,7,10-tetraoxa-6-silaundecane and trimethoxy[3-(oxiranylmethoxy)propyl]silane (9CI) (CA INDEX NAME)

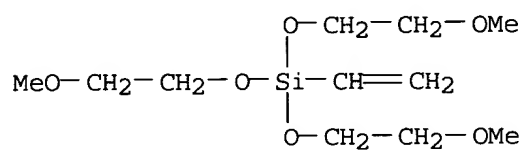
CM 1

CRN 2530-83-8
CMF C9 H20 O5 Si



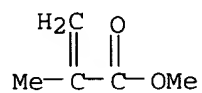
CM 2

CRN 1067-53-4
CMF C11 H24 O6 Si



CM 3

CRN 80-62-6
CMF C5 H8 O2


$$\Rightarrow$$